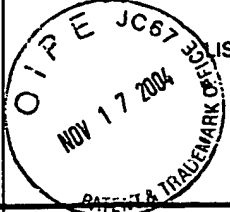


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-2310		SERIAL NO. Unknown	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT: Brenda D. Kraus et al.			
					FILING DATE Filed Herewith		GROUP Unknown	
U.S. PATENT DOCUMENTS								
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
EF	AA	10/133,947		Vaartstra			04/25/2002	
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	AH							
	AI							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ							
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
EF	AM	Baghurst et al., <i>Microwave syntheses for superconducting ceramics</i> , 332 NATURE 11 (March 24, 1988).						
EF	AN	Kuo et al., <i>Microwave-assisted chemical vapor deposition process for synthesizing carbon nanotubes</i> ,						
		J. VAC. SCI. TECHNOL., Vol. 19, No. 3, pp. 1030-1033 (May/June 2001).						
	AO							
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2310	SERIAL NO. 10/643,680			
				APPLICANT: Kraus et al.				
				FILING DATE August 18, 2003	GROUP 1762			
U.S. PATENT DOCUMENTS								
Examiner's Initials	Class	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
EF	AA	6,511,539	01/2003	Raaijmakers	117	102		
EF	AB	6,576,053	06/2003	Kim et al.	117	89		
EF	AC	6,753,618	06/2004	Basceri et al.	257	915		
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EF	AG	2003/0049931 A1	03/2003	Byun et al.	438	649		
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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
EF	AJ	WO 01/27346 A1	04/2001	WIPO				
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EF	AM	Juppo et al., "Use of 1,1-Dimethylhydrazine in the Atomic Layer Deposition of Transition Metal Nitride Thin Films", <i>Journal of the Electrochemical Society</i> , 147 (9), 2000, p. 3377-3381.						
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EF	AN	J. W. Klaus et al., Atomic Layer Deposition of Tungsten Nitride Films Using Sequential Surface Reactions", <i>Journal of the Electrochemical Society</i> , 147 (3), 2000, p. 1175-1181.						
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT: Kraus et al.			
					FILING DATE August 18, 2003		GROUP 1762	
U.S. PATENT DOCUMENTS								
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
EF	AA	2003/0168750 A1	09/2003	Basceri et al.	257	915		
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	AC							
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	AI							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT: Kraus et al.			
					FILING DATE August 18, 2003		GROUP 1762	
U.S. PATENT DOCUMENTS								
Examiner's Initials	Class	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
EF	AA	6,863,725	03/05	Vaartstra et al.				
EF	AB	6,730,164	05/04	Vaartstra et al.				
EF	AC	6,730,163	05/04	Vaartstra et al.				
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FOREIGN PATENT DOCUMENTS								
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OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
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